

SIC MATERIAL AND SIC COMPOSITE MATERIAL

[ABSTRACT]

The present invention relates to an SiC material and an SiC composite material and, more particularly, to an SiC material and an SiC composite material having a diffraction intensity ratio (I) of an X-ray diffraction peak, calculated by formula 1 down below, of less than 1.5. The present invention can provide an SiC material and an SiC composite material which can be etched evenly when exposed to plasma and thereby reduce the occurrence of cracks, holes and so forth. [Formula 1] Diffraction intensity ratio (I) = (peak intensity of plane (200) + peak intensity of plane (220)) / peak intensity of plane (111).

FIG. 1C